

Detection of Radicals and Reactive Species Formed in Wafer Cleaning Solutions Irradiated with Megasonic Waves

(Task Number: 2324.001.)

PIs:

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Other Researchers:

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Cost Share (other than core ERC funding):

- **Donation of Cavitation Threshold (CT) cell and MegBowl from ProSys, Inc., \$30k**

Objectives and Methods of Approach

Objectives

- **Validate the existence of hydroperoxyl ($\text{HO}_2\cdot$) radicals in liquid medium irradiated by megasonic waves**
- **Quantify the rate of generation of $\text{H}\cdot$ radicals in a megasonic field**

Tasks

- ***Sub-task 1:* In-situ detection of $\text{HO}_2\cdot$ using a chemiluminescence (CL) technique**
- ***Sub-task 2:* Estimation of the generation rate of $\text{H}\cdot$ radicals in a megasonic field using chronoamperometry**

ESH Metrics and Impact

- **Control of concentration of active radicals through megasonic input would allow *in situ* generation of cleaning power, thus leading to reduction in the use of “bulk” cleaning chemicals.**

Sub-task 1: In-situ detection of HO₂· using a chemiluminescence (CL) technique

Method of Approach

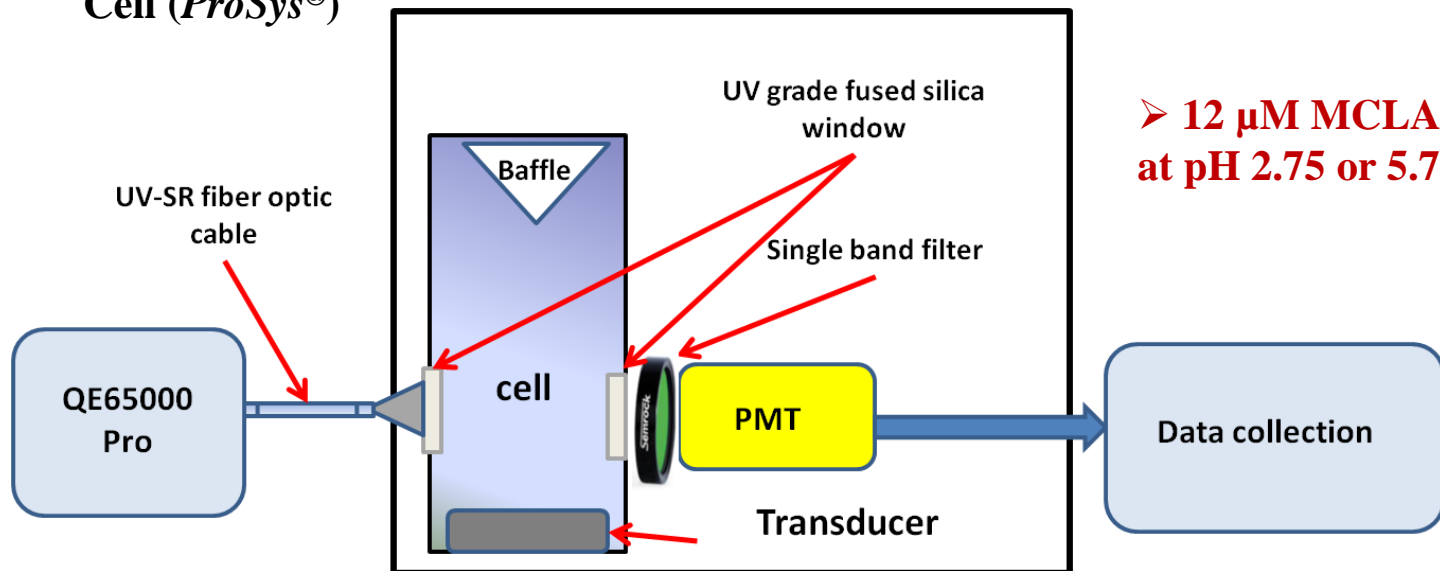
- Detection of hydroperoxyl radicals was done using a chemiluminescence (CL) method; **MCLA** (2-methyl-6-(p-methoxyphenyl)-3,7-dihydroimidazo[1,2-a]pyrazine-3-one) was used as the CL probe* .
- The complex between MCLA and hydroperoxyl radical emits light in the wavelength range of **457 to 465 nm**.
- CL emission was captured and analyzed by a spectrometer

*Y. Kambayashi and K. Ogino, Reestimation of cypridina luciferin analogs (MCLA) as a chemiluminescence probe to detect active oxygen species, J of Toxicological Sciences, Vol. 28 (3), pp. 139-148 (2003)

Schematic of the Experimental Set-up

Cavitation Threshold (CT)

Cell (*ProSys*[®])



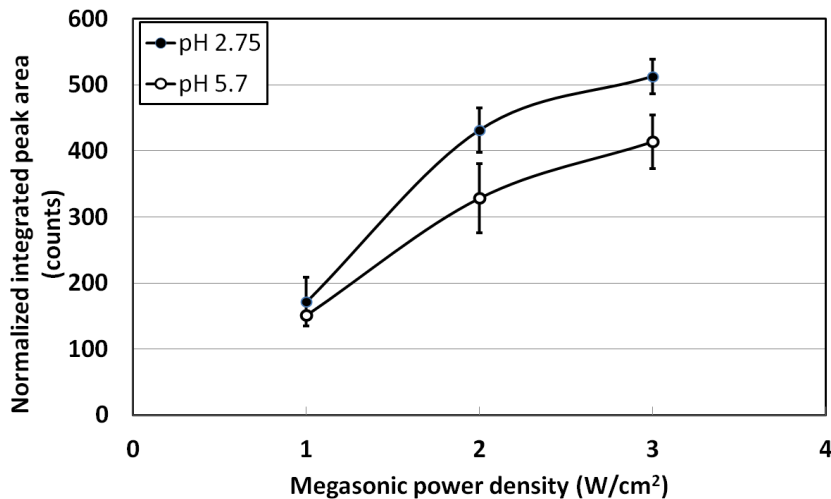
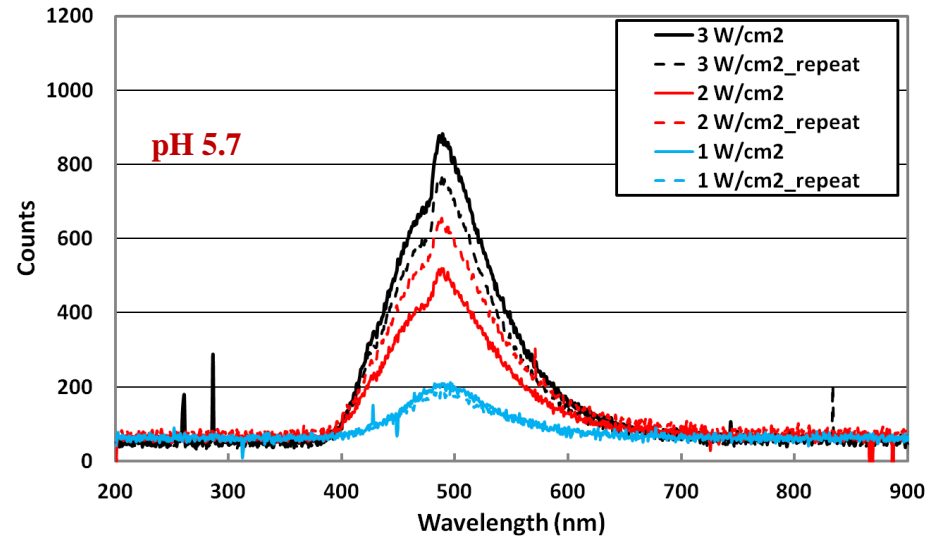
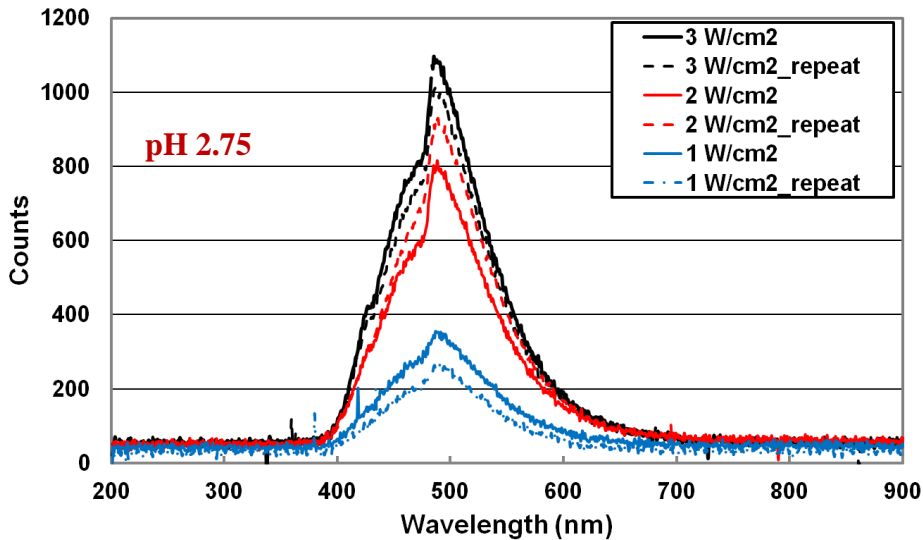
➤ **12 μ M MCLA in 1:100 ethanol : DIW at pH 2.75 or 5.7**

CT Cell Details

- *Volume = 163 cc, Length = 10.4 cm*
 - *Internal Diameter = 4.8 cm*
 - *Sonic Frequency = 0.925 MHz*
- *PMT Wavelength Range = 280 to 630 nm*
- *Power Density Range = 0.1 to 4 W/cm²*

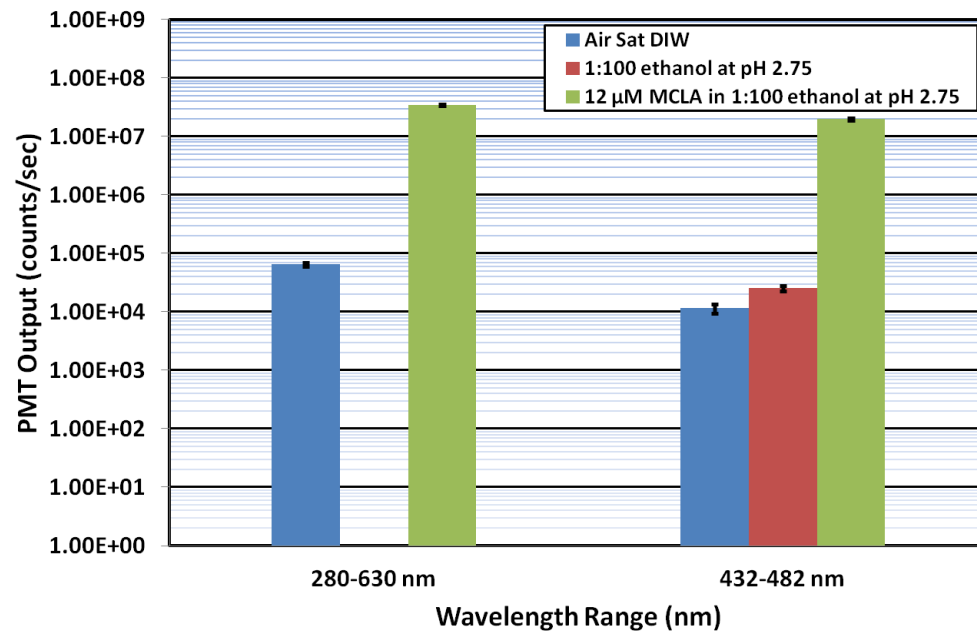
- **Spectrometer: QE65000 Pro (Ocean Optics)**
- **FO cable: UV-SR (11 cm)**
- **Spectral acquisition time: 2 min**
- **Single band filters:**
 1. **300~340 nm**
 2. **432~482 nm**

Effect of Megasonic Power Density on CL Intensity



- The intensity of CL is a function of megasonic power density and solution pH
- Emission peak at 480 nm
- Results confirm the existence of HO₂•

Confirmation of Emission from MCLA Complex with Hydroperoxyl Radicals from Sonoluminescence Signal Measured using PMT



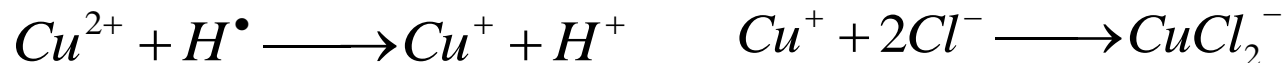
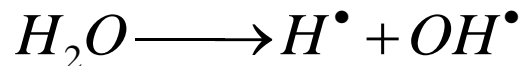
1 W/cm²

- In solutions containing MCLA, PMT output is dominated by emission in the wavelength range of 432 to 482 nm; this proves the existence of MCLA-HO₂ complex

Sub-task 2: Estimation of the generation rate of H· radicals in a megasonic field using chronoamperometry

Method of Approach

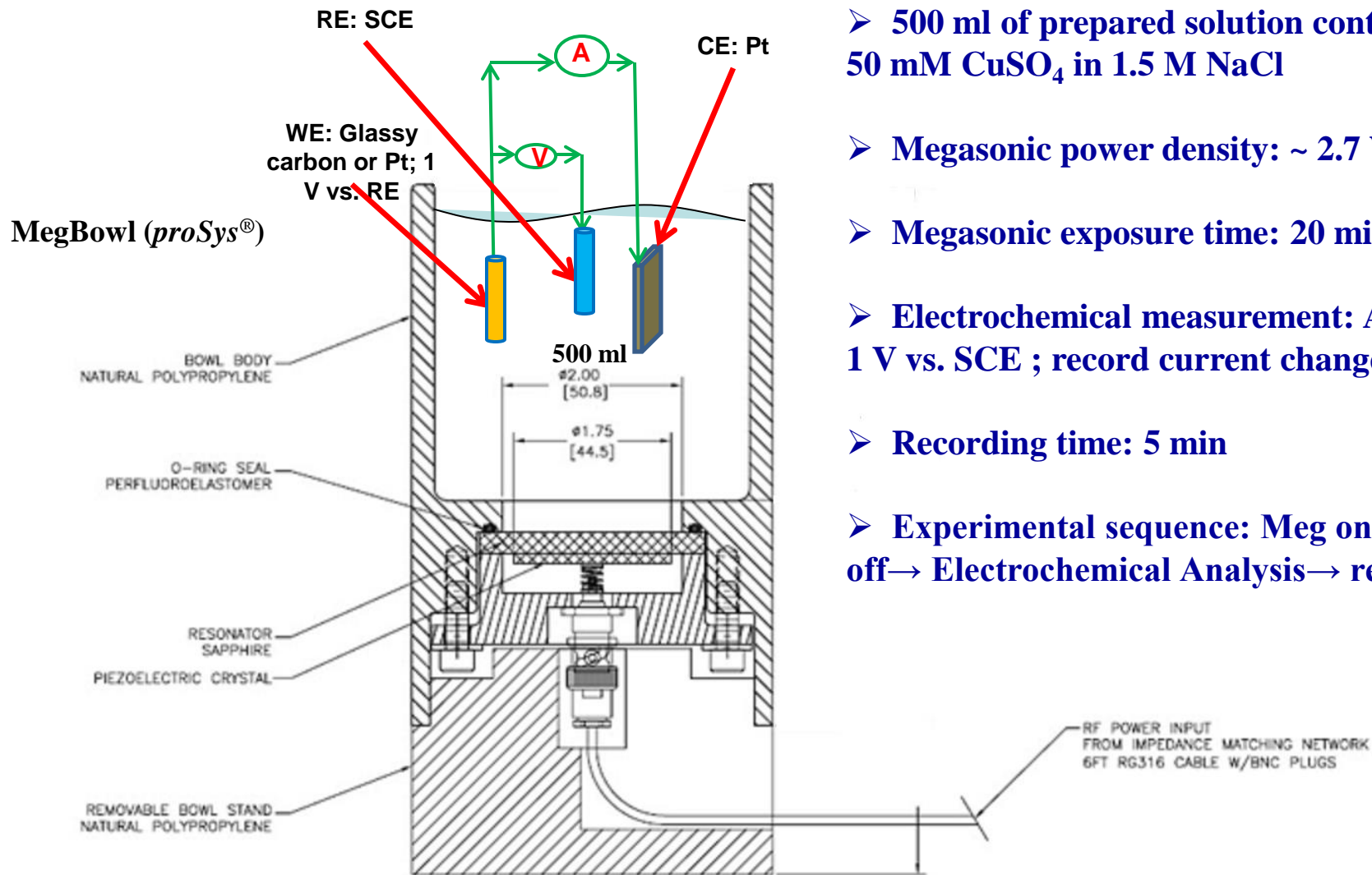
- Hydrogen radicals (H·) generated during megasonic irradiation can reduce Cu²⁺ ions to cuprous ions (Cu⁺); in the presence of excess chloride ions, Cu⁺ will be converted to CuCl₂⁻



- Generation rate of CuCl₂⁻ is equal to the generation rate of H· (assuming no other routes exist for the consumption of H·)
- CuCl₂⁻ can be measured by electrochemical oxidation to Cu²⁺

P. R. Birkin, J. F. Power and T. G. Leighton, Electrochemical evidence of H· by ultrasound, Chem. Commun., pp. 2230-2231 (2001)

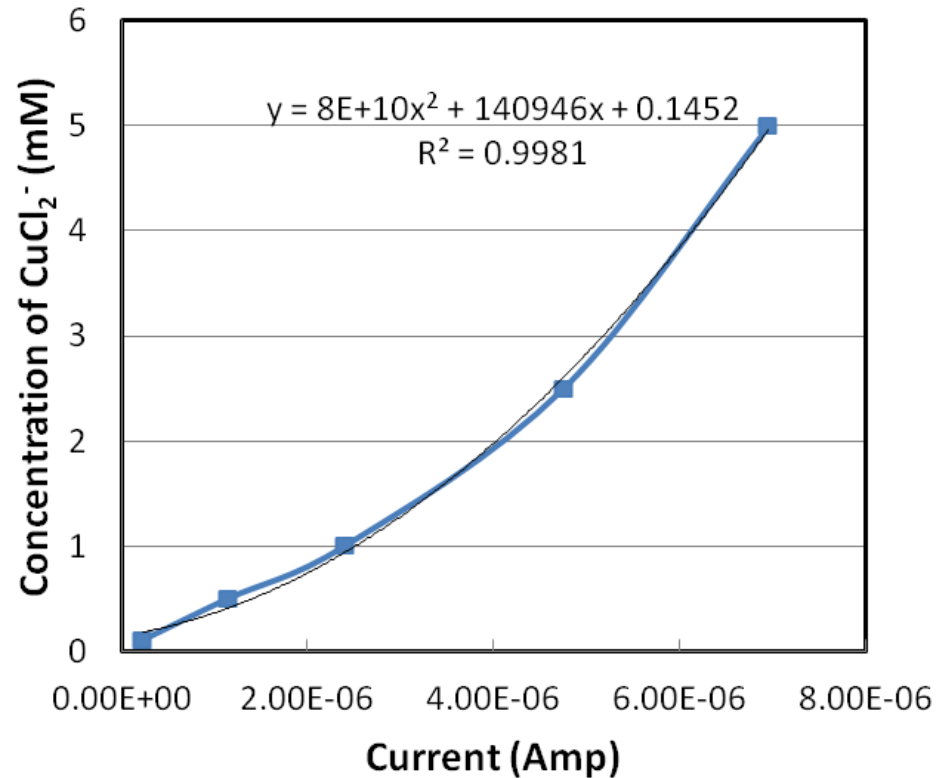
Schematic of Electrochemical Set-up in MegBowl



- 500 ml of prepared solution containing 50 mM CuSO₄ in 1.5 M NaCl
- Megasonic power density: ~ 2.7 W/cm²
- Megasonic exposure time: 20 min
- Electrochemical measurement: Apply 1 V vs. SCE ; record current change
- Recording time: 5 min
- Experimental sequence: Meg on → Meg off → Electrochemical Analysis → repeat

Calibration Curve for CuCl_2^-

Concentration of CuCl_2^- (mM)	Current at 300 sec (Amp)
5	$6.95 \pm 0.45 \text{E-}06$
2.5	$4.75 \pm 0.01 \text{E-}06$
1	$2.40 \pm 0.13 \text{E-}06$
0.5	$1.15 \pm 0.02 \text{E-}06$
0.1	$2.25 \pm 0.03 \text{E-}07$



➤ Standard solutions containing CuCl_2^- were prepared from CuCl(s)

Calculated H· Generation Rate in 50 mM CuSO₄ solution When exposed to Megasonic Field at 2.7 W/cm²

Megasonic exposure time (min)	Current at 300 sec (Amp)	CuCl ₂ ⁻ concentration (mM)	CuCl ₂ ⁻ generation rate (mM/s)	CuCl ₂ ⁻ generation rate (nM/s)	H· generation rate (nM/s)	Solution temp. (degree C)
20	6.35E-07	2.67E-01	8.12E-05	~ 80		42.0
	5.28E-07	2.42E-01	7.54E-05	~ 75	71 ± 12	42.0
	4.35E-07	2.22E-01	5.79E-05	~ 58		41.2

- H· generation rate in the range of **71 ± 12** nM/s at 2.7 W/cm²
- After 20 min megasonic exposure, solution temperature increased to be ~ 40 degree C
- In 125 Hz ultrasonic field, the generation rate of H· has been reported to be 400 nM/s at 6 W/cm²

Summary

- Developed an *in-situ* chemiluminescence (CL) based detection method for $\text{HO}_2\cdot$ generated in megasonic field. CL intensity increases with megasonic power density.
- Using an electrochemical method, estimated the generation rate of $\text{H}\cdot$ in 2.7 W/cm^2 megasonic field to be $70 \pm 10 \text{ nM/s}$.

Industrial Interactions and Technology Transfer

- **Technical discussions with Dr. Ian Brown (TEL/AMAT)**

Future Plans

Plans for the remainder of the contract period

- **Measure the generation rate of hydrogen radicals in basic cleaning solutions at different power densities**

Publications, Presentations, and Recognitions/Awards

- **M. Keswani, S. Raghavan, R. Govindarajan and I. Brown, Measurement of hydroxyl radicals in wafer cleaning solutions irradiated with megasonic waves, *Microelectronic Engineering* (2013), in press, <http://dx.doi.org/10.1016/j.mee.2013.12.028>.**
- **Z. Han and S. Raghavan, *In-situ* chemiluminescence (CL) based detection and quantitation of hydroperoxyl radicals in aqueous solutions under megasonic irradiation, invention disclosure filed with Tech Launch Arizona.**
- **M. Keswani, S. Raghavan, I. Brown, Measurement of hydroxyl radicals in wafer cleaning solutions irradiated with megasonic field, presented at Sematech *SPCC* conference, Austin, TX, Apr. 4th, 2013.**